

Title (en)

SCRATCH-RESISTANT REAR PROJECTION SCREEN AND METHOD FOR PRODUCING THE SAME

Title (de)

KRATZUNEMPFINDLICHER RÜCKPROJEKTIONSSCHIRM UND VERFAHREN ZU DESSEN HERSTELLUNG

Title (fr)

ECRAN DE RETROPROJECTION RESISTANT AUX RAYURES ET SON PROCEDE DE PRODUCTION

Publication

EP 1652001 A1 20060503 (DE)

Application

EP 04719963 A 20040312

Priority

- EP 2004002599 W 20040312
- DE 10336129 A 20030804

Abstract (en)

[origin: DE10336129A1] A back projection screen comprises at least one light scattering polymethylmethacrylate layer comprising a polymethylmethacrylate matrix and spherical particles (A) and spherical particles (B) having different average particle sizes with at least one particle type having a refractive index that is different to that of polymethylmethacrylate matrix. A back projection screen (I) comprises at least one light scattering polymethylmethacrylate layer comprising a polymethylmethacrylate matrix and spherical particles (A) and spherical particles (B) having different average particle sizes whereby (A) have an average particle size of 0.1-40 μm and a refractive index that is different to that of polymethylmethacrylate matrix by 0.02-2 and (B) have an average particle size of 10-150 μm and a refractive index that is different to that of polymethylmethacrylate matrix by 0-0.2 and the total concentration of (A) and (B) is 1-60 wt. % (with respect to the light scattering polymethylmethacrylate layer) such that the ratio of the concentration of particles (A) CPA, thickness of the light scattering layer d s and particle size of (A) DPA as defined by CPA.ds/DPA3 is 0.001-0.015 wt.%. $\text{mm}/\mu\text{m}^3$ and the corresponding ratio for particles (B), CPB.ds /DPB3 is 0.000005-0.002 wt.%. $\text{mm}/\mu\text{m}^3$ and the ratio of the square of the average surface roughness of the polymethylmethacrylate layer R z to the cube of the particle size of (B) R 2> z/DPB3 is 0.0002-0.1300 μm -> 1>. An independent claim is included for a process for the production of the screen (I) by extrusion of a composition comprising polymethylmethacrylate, particles (A) and particles (B).

IPC 1-7

G03B 21/62; G02B 5/02

IPC 8 full level

G02B 5/02 (2006.01)

CPC (source: EP KR US)

G02B 5/0221 (2013.01 - EP KR US); **G02B 5/0242** (2013.01 - EP KR US); **G02B 5/0278** (2013.01 - EP KR US);
G02B 5/0294 (2013.01 - EP KR US); **G02B 30/56** (2020.01 - KR); **G03B 21/62** (2013.01 - EP KR US)

Citation (search report)

See references of WO 2005022253A1

Designated contracting state (EPC)

AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HU IE IT LI LU MC NL PL PT RO SE SI SK TR

DOCDB simple family (publication)

DE 10336129 A1 20050224; AU 2004269461 A1 20050310; AU 2004269461 B2 20090910; CA 2533510 A1 20050310;
CN 1823300 A 20060823; EP 1652001 A1 20060503; EP 2339398 A1 20110629; JP 2007501423 A 20070125; KR 20060120575 A 20061127;
MX PA06001066 A 20060411; RU 2006106613 A 20070920; RU 2343521 C2 20090110; RU 2343521 C9 20100120; TW 200509683 A 20050301;
US 2006209403 A1 20060921; US 7339732 B2 20080304; WO 2005022253 A1 20050310

DOCDB simple family (application)

DE 10336129 A 20030804; AU 2004269461 A 20040312; CA 2533510 A 20040312; CN 200480020097 A 20040312; EP 04719963 A 20040312;
EP 08168820 A 20040312; EP 2004002599 W 20040312; JP 2006522238 A 20040312; KR 20067002424 A 20060203;
MX PA06001066 A 20040312; RU 2006106613 A 20040312; TW 93107328 A 20040318; US 56624404 A 20040312